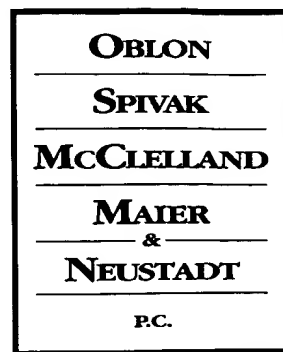




Docket No.: 215930US99

COMMISSIONER FOR PATENTS
ALEXANDRIA, VIRGINIA 22313



ATTORNEYS AT LAW

RE: Application Serial No.: 09/986,899

Applicants: Dirk C. JORDAN, et al.

Filing Date: November 13, 2001

For: STRUCTURE AND METHOD FOR FABRICATING
SEMICONDUCTOR STRUCTURES AND DEVICES
UTILIZING THE FORMATION OF A COMPLIANT
SUBSTRATE HAVING A NIOBIUM
CONCENTRATION

Group Art Unit: 2814

Examiner: WILLE

SIR:

Attached hereto for filing are the following papers:

**REQUEST FOR RECONSIDERATION; REQUEST FOR EXTENSION OF
TIME (two-month)**

Our check in the amount of \$410.00 is attached covering any required fees. In the event any variance exists between the amount enclosed and the Patent Office charges for filing the above-noted documents, including any fees required under 37 C.F.R. 1.136 for any necessary Extension of Time to make the filing of the attached documents timely, please charge or credit the difference to our Deposit Account No. 15-0030. Further, if these papers are not considered timely filed, then a petition is hereby made under 37 C.F.R. 1.136 for the necessary extension of time. A duplicate copy of this sheet is enclosed.

Respectfully submitted,

OBLON, SPIVAK, McCLELLAND,
MAIER & NEUSTADT, P.C.

Richard L. Treanor

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DOCKET NO.: 215930US99

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE



IN RE APPLICATION OF:

: GROUP ART UNIT: 2814

DAVID C. JORDAN ET AL

:

SERIAL NO.: 09/986,899

:

EXAMINER: WILLE, D.A.

FILED: NOVEMBER 13, 2001

:

FOR: STRUCTURE AND METHOD FOR FABRICATING SEMICONDUCTOR
STRUCTURES AND DEVICES UTILIZING THE FORMATION OF A
COMPLIANT SUBSTRATE HAVING A NIOBIUM CONCENTRATION

REQUEST FOR RECONSIDERATION

COMMISSIONER FOR PATENTS
ALEXANDRIA, VA 22313

SIR:

Responsive to the Official Action dated December 11, 2002, Applicants respectfully
request reconsideration in view of the following remarks.

REMARKS

Applicants very much appreciate the indication of allowable subject matter in this
case, and the recognition that the applied prior art does not show a graded Nb concentration
or a template layer, does not show the formation of an amorphous accommodating layer, the
high levels of Nb doping, or the specific thickness of the accommodating layer in the
allowable claims.

As the Examiner is probably already aware, the present application is part of the
Motorola "bulk filing applications." Two IDSs have been filed in this case using special
procedures granted by Petition.

#9/ Response
Ariel
5/17/03

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